

# Notice of Allowability

Application No.

10/725,055

Examiner

W. Patty Chen

Applicant(s)

LIM, BYOUNG HO

Art Unit

2871

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to Amendment filed on 4/19/07.
2. ☒ The allowed claim(s) is/are 1-9, 11-13 and 20.
3. ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
  - a) ☒ All b) ☐ Some\* c) ☐ None of the:
    1. ☒ Certified copies of the priority documents have been received.
    2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
    3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

\* Certified copies not received: \_\_\_\_\_.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.

**THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.**

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
  5. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
    - (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
      - 1) ☐ hereto or 2) ☐ to Paper No./Mail Date \_\_\_\_\_.
    - (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date \_\_\_\_\_.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

## Attachment(s)

1. ☐ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO/SB/08);  
Paper No./Mail Date \_\_\_\_\_
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material
5. ☐ Notice of Informal Patent Application
6. ☐ Interview Summary (PTO-413),  
Paper No./Mail Date \_\_\_\_\_
7. ☒ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☐ Other \_\_\_\_\_

## **DETAILED ACTION**

### ***Continued Examination Under 37 CFR 1.114***

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on Apr. 19, 2007 has been entered.

### ***Response to Amendment.***

Applicant's Amendment filed on Apr. 19, 2007 has been entered. Claim 10 is cancelled and claim 20 is newly added per the Amendment filed. Therefore, claims 1-9 and 11-20 are now pending in the current application and claims 14-19 are withdrawn from consideration.

### ***Election/Restrictions***

This application is in condition for allowance except for the presence of claims 14-19 directed to Invention non-elected without traverse. Accordingly, claims 14-19 have been cancelled.

## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR

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1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with the Attorney for Applicant on Aug. 28, 2007.

The Specification of the application, specifically Paragraphs 0025-0026 on Pages 8 and 9, has been amended as follows:

FIG. 1 is a cross sectional view of a method for fabricating a liquid crystal display device using a four masks process according to the related art;

FIG. 2 is a cross sectional view of a method for fabricating a liquid crystal display device using a four masks process according to the related art;

FIG. 3 is a cross sectional view of a method for fabricating a liquid crystal display device using a four masks process according to the related art;

FIG. 4 is a cross sectional view of a method for fabricating a liquid crystal display device using a four masks process according to the related art;

FIG. 5 is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 6A is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 6B is a plane view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 7 is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 8 is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 9A is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 9B is a plane view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 10A is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 10B is a plane view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 11 is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 12A is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 12B is a plane view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 13A is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 13B is a plane view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 14 is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

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FIG. 15A is a cross sectional view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention;

FIG. 15B is a plane view of an exemplary method for fabricating a liquid crystal display device using three masks process according to the present invention; and

***Allowable Subject Matter***

Claims 1-9, 11-13 and 20 are allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claim 1: None of the prior arts teach or suggested either alone or in combination the forming of a second organic material film on the passivation film and to expose a second portion of the gate pad and a first portion of the data pad by removing the second organic material using a lift-off process. Kim et al. (US 5731856) teach forming a passivation layer and then an organic layer to expose the gate and data pads by photolithography.

Therefore, claim 1 is allowed over the prior arts.

As to claims 2-6: Since claims 2-6 are dependent either directly or indirectly on claim 1, therefore are also allowed.

Regarding claim 7 (Amended): None of the prior arts teach or suggested either alone or in combination the forming of an organic material film on the gate and data pads after patterning the transparent conductive film that forms the data bus line, the data pad, the source electrode, the drain electrode and the pixel electrode and the passivation layer is then formed on the entire surface of the substrate including the organic material film.

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Therefore, claim 7 is deemed non-obvious and inventive over the prior arts, thus is allowed.

As to claims 8-9, 11-13 and 20 (New): Since claims 8-9, 11-13 and 20 depend either directly or indirectly on the allowed claim 7, hence are also allowed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

### ***Conclusion***

Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. Patty Chen whose telephone number is (571)272-8444. The examiner can normally be reached on 8:00-5:00 M-F.

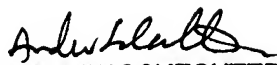
If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on (571)272-1787. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

W. Patty Chen  
Examiner  
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WPC  
8/28/07

  
ANDREW SCHECHTER  
PRIMARY EXAMINER